

CERTIFICATE OF MAILING

I hereby certify that this Amendment is being deposited with the United States Postal Service on September 13, 2000 with sufficient postage as first class mail in an envelope addressed to the Assistant Commissioner for Patents, Washington, D.C. 20231.

Martha L. Blevins
Martha L. Blevins

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



There application of: Darryl W. Peters, et al.

Art Unit: 1751

Serial No.: 09/238,851

Examiner: G. Webb

Filed: 01/27/99

Docket No.: 5545

Title: LOW SURFACE TENSION, LOW VISCOSITY, AQUEOUS ACIDIC COMPOSITIONS CONTAINING FLUORIDE AND ORGANIC, POLAR SOLVENTS FOR REMOVAL OF PHOTORESIST AND ORGANIC AND INORGANIC ETCH RESIDUES AT ROOM TEMPERATURE

G/WB
11-1-00

Assistant Commissioner for Patents
Washington, D. C. 20231

AMENDMENT

Dear Sir:

Following is a response to the Official Office Action dated March 14, 2000.
Attached is a petition for a three-month extension of time. Kindly amend the specification as follows:

In the Claims:

P/S/DP

14. (amended) A method of removing photoresist or residue from a substrate, comprising; applying a composition according to claim 1 to the substrate at a temperature of from 20°C to 80°C for a period of time sufficient to remove the [coating] photoresist or residue from the substrate.

Remarks

Claim 14 has been amended. The term "coating" has been deleted and "photoresist or residue" has been inserted in its place. No new matter has been

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